

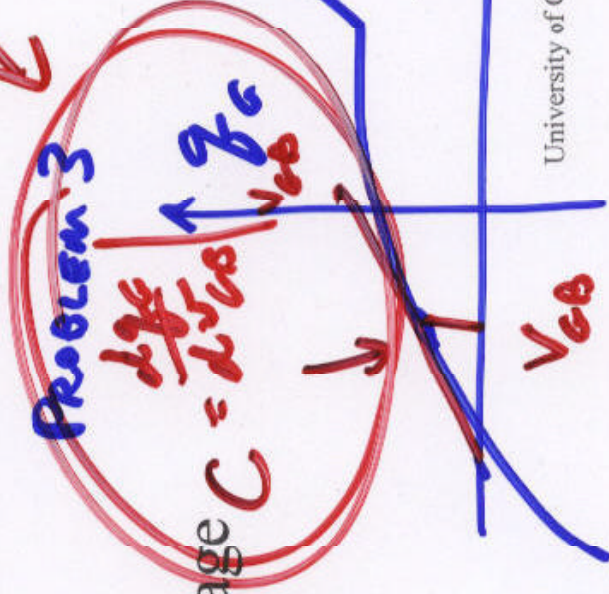
Lecture 12

- Last time:
 - pn junction *small-signal* capacitance
 - start MOS structure

ALL YOU
NEED:

- Today :

- MOS charge storage
- MOS capacitor





~~PEC~~ ~~v_T~~

D.C.

MOS Structure

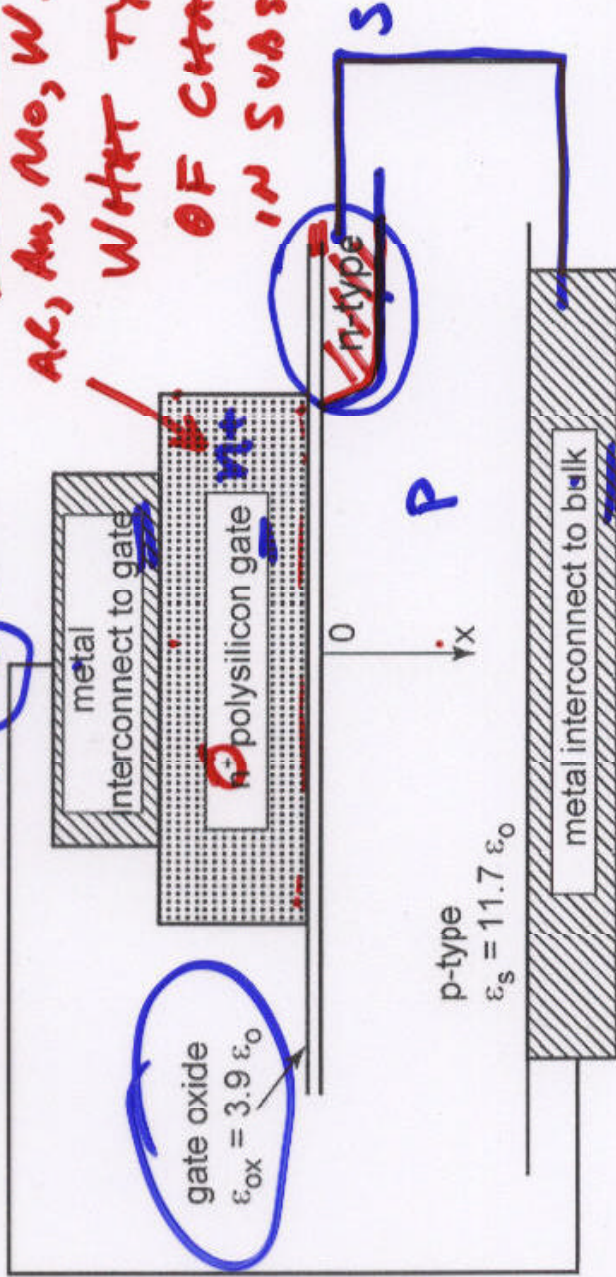
$I_G = 0$

CHARGE-STORAGE ELEMENT

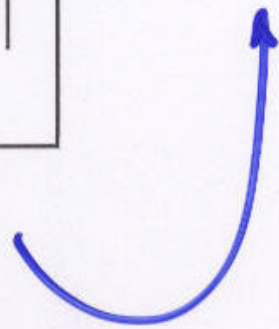
AL, Au, Mo, W.

WHAT TYPE

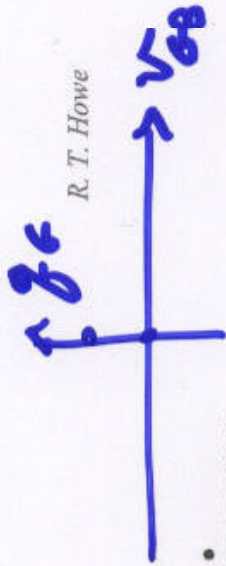
OF CHARGE...
IN SUBSTRATE.



CAPACITANCE / AREA.

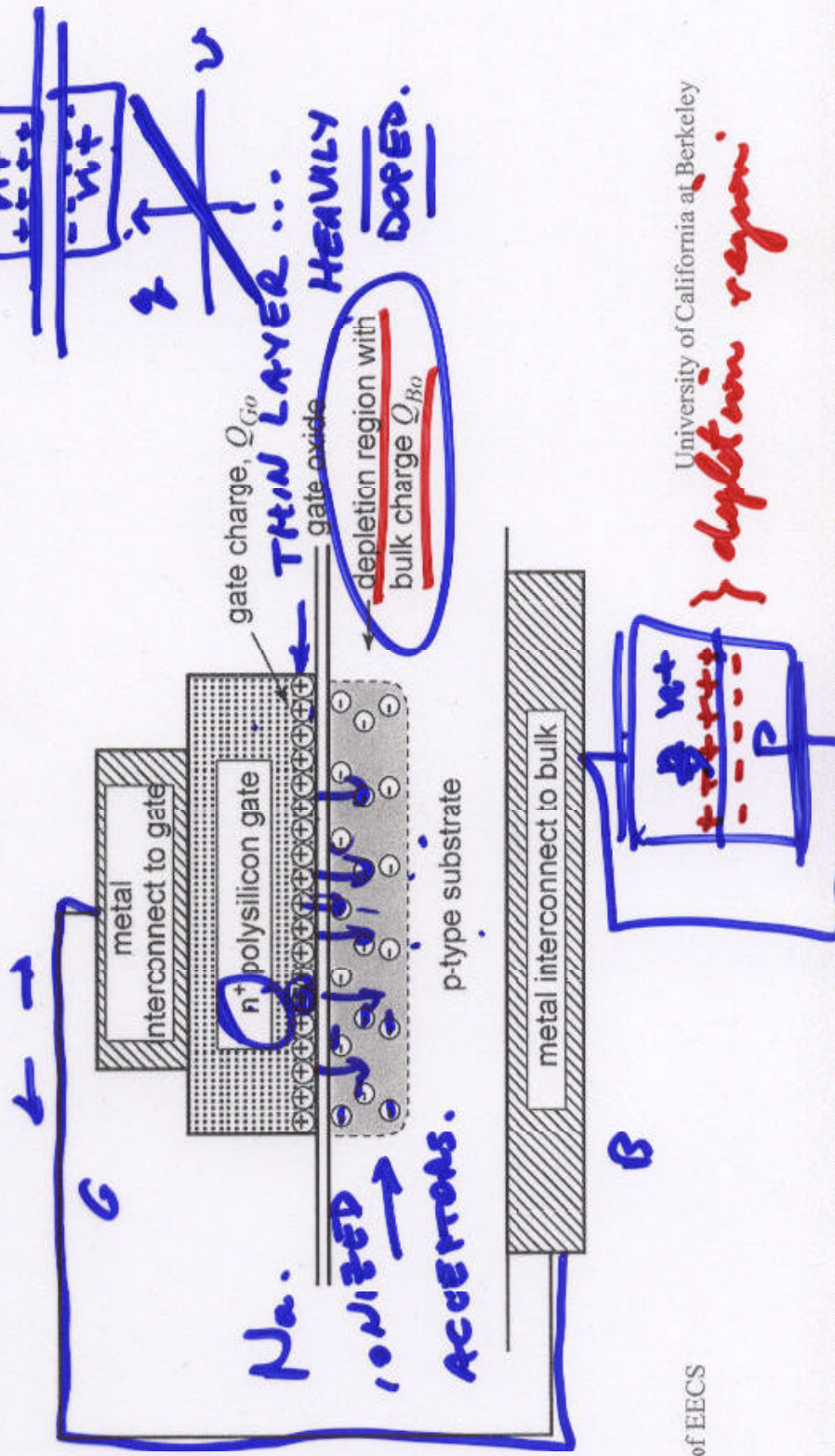


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Thermal Equilibrium.

Charged bi-layer forms: + charges on gate, - in substrate
 Built-in voltage between gate and substrate



Applying a DC Voltage V_{GB}

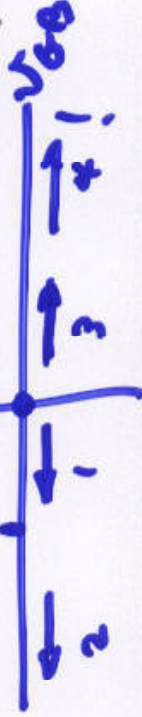
Goal: find out how the gate charge Q_G varies as a function of the applied voltage V_{GB}

Procedure: start at thermal equilibrium. $V_{GB} = 0V$.

- (i) go negative until built-in charge is cancelled.
- (ii) keep going until charge on gate is negative
- (iii) go positive from thermal equilibrium
- (iv) keep increasing V_{GB} until ...

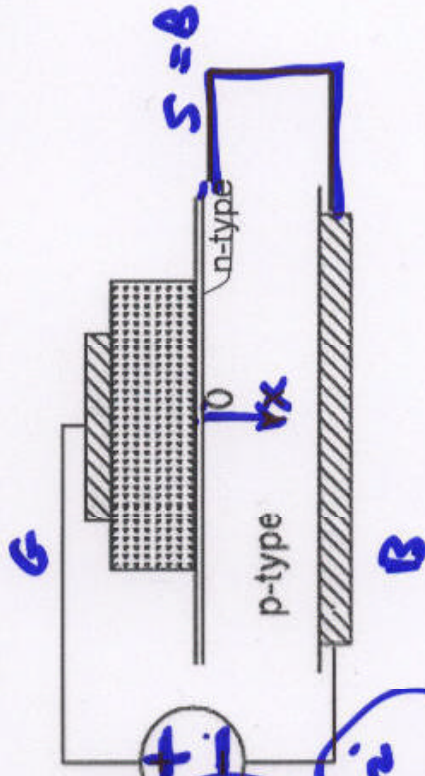
~~WHAT ARE THEY?~~

IMPORTANT: IDENTIFY CHARGE IN SUBSTRATE



Cancel the Built-in Voltage

$$\frac{\text{Triangular Equil. } n}{\frac{KX}{S} = 0}$$

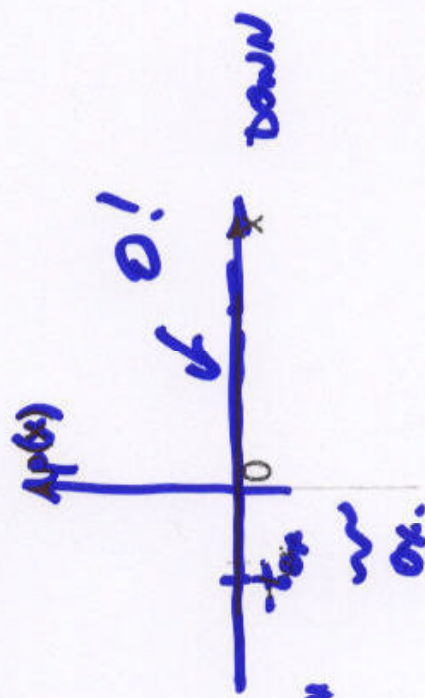


Apply V_{FB} to "zero" the built-in voltage

$$V_{GB} = V_{FB}$$

$$V_{GB} = -0.2$$

$$= -0.3$$



$$V_{GB} < 0$$

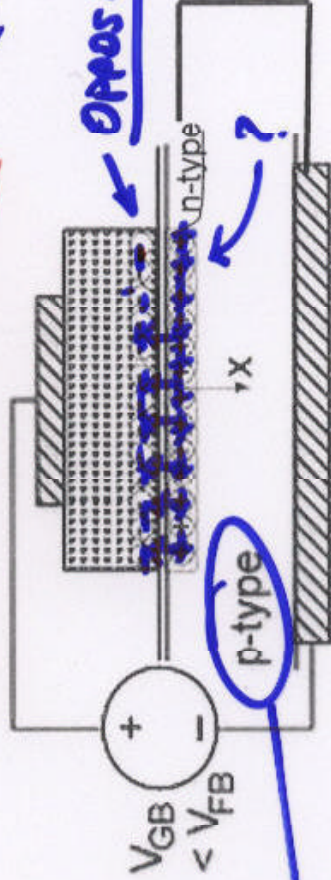
$$V_{FB} = \text{"flat band" voltage.}$$

$$= -0.9 \text{ V.}$$

①

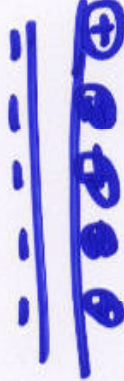
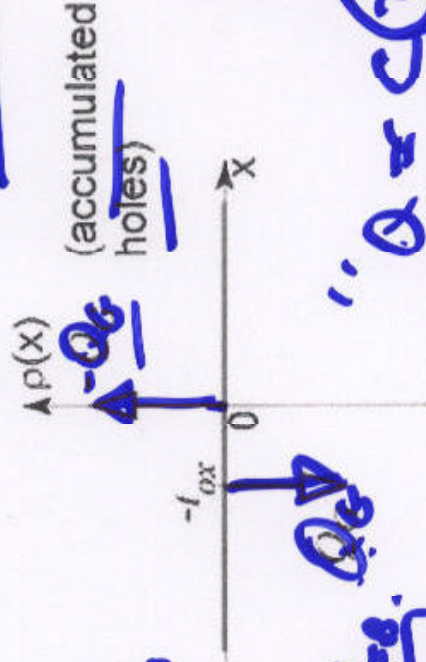
$V_{GS} < V_{FB} (\approx -0.9V)$

Accumulation



- DOPED WITH $\beta \dots$ NEGATIVE CHARGES \dots HOLES! mobile, + charge.

"METAL-METAL CAP."



TRUE FOR $V_{GS} < V_{FB}$

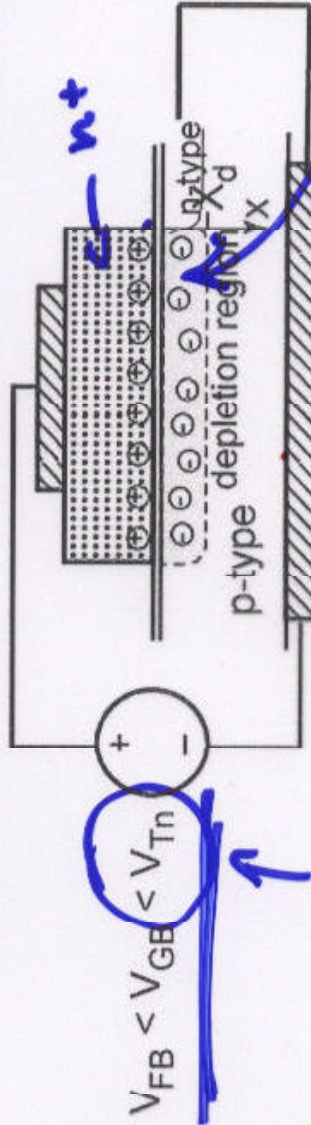
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$Q_G = C_{ox} (V_{GS} - V_{FB}) C = C_{ox} \rightarrow \approx 4 \frac{\epsilon_0}{t_{ox}} \dots$

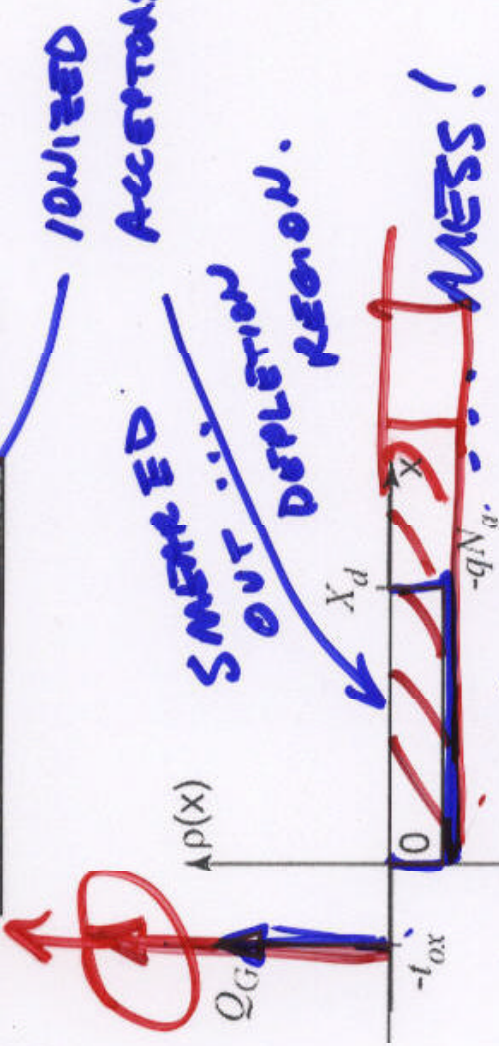
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$0 > V_{FB} \approx -0.8V$ SAME AS THRESHOLD EQUATION!

3 Depletion: $V_{GB} > V_{FB}$



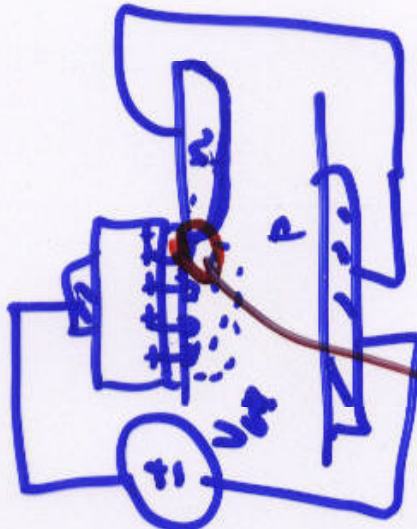
$V_{FB} < V_{GB} < V_{Tn}$



$Q_G = f(V_{GB})$
For $V_{GB} > V_{FB}$

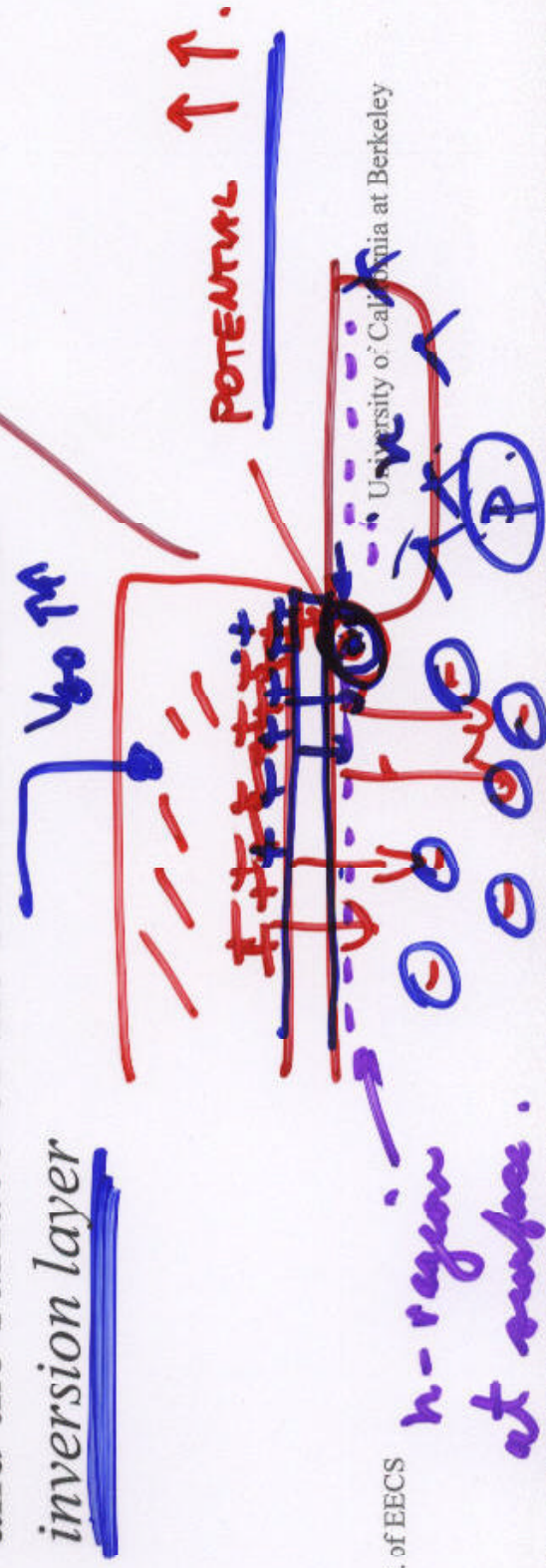
at $V_{GB} \approx 1V \dots$ SUMMARY!
 $V_{GB} = 0, 0.5, 1, 1.5, 2, \dots, 20V$

What Happens as V_{GB} Increases?



Vertical E field increases at the surface, lowering the barrier between the n-type region next to the gate and the channel underneath it ...

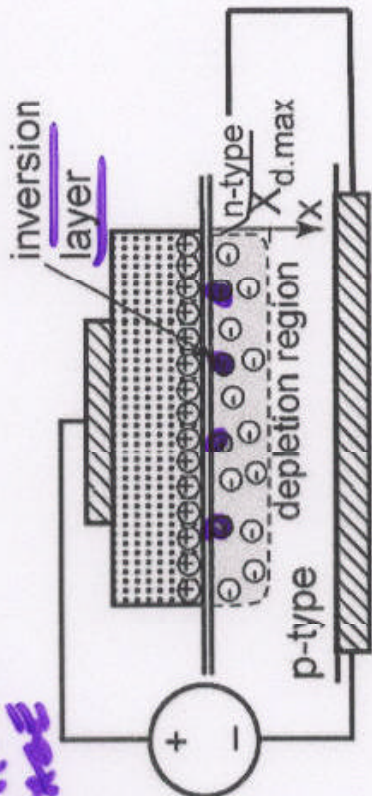
eventually (at $V_{GB} = V_{Tn}$), electrons flood in and the surface of the substrate has an inversion layer



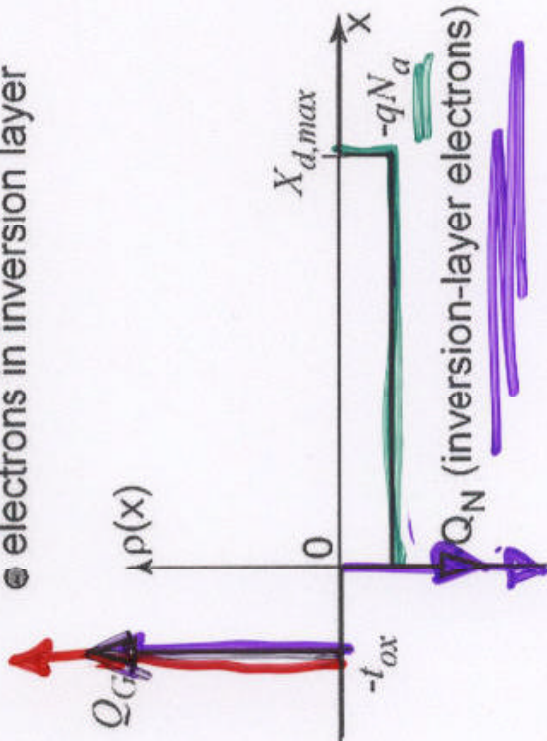
MOS Capacitor in Inversion

THRESHOLD VOLTAGE

$V_{GB} > V_{Tn}$

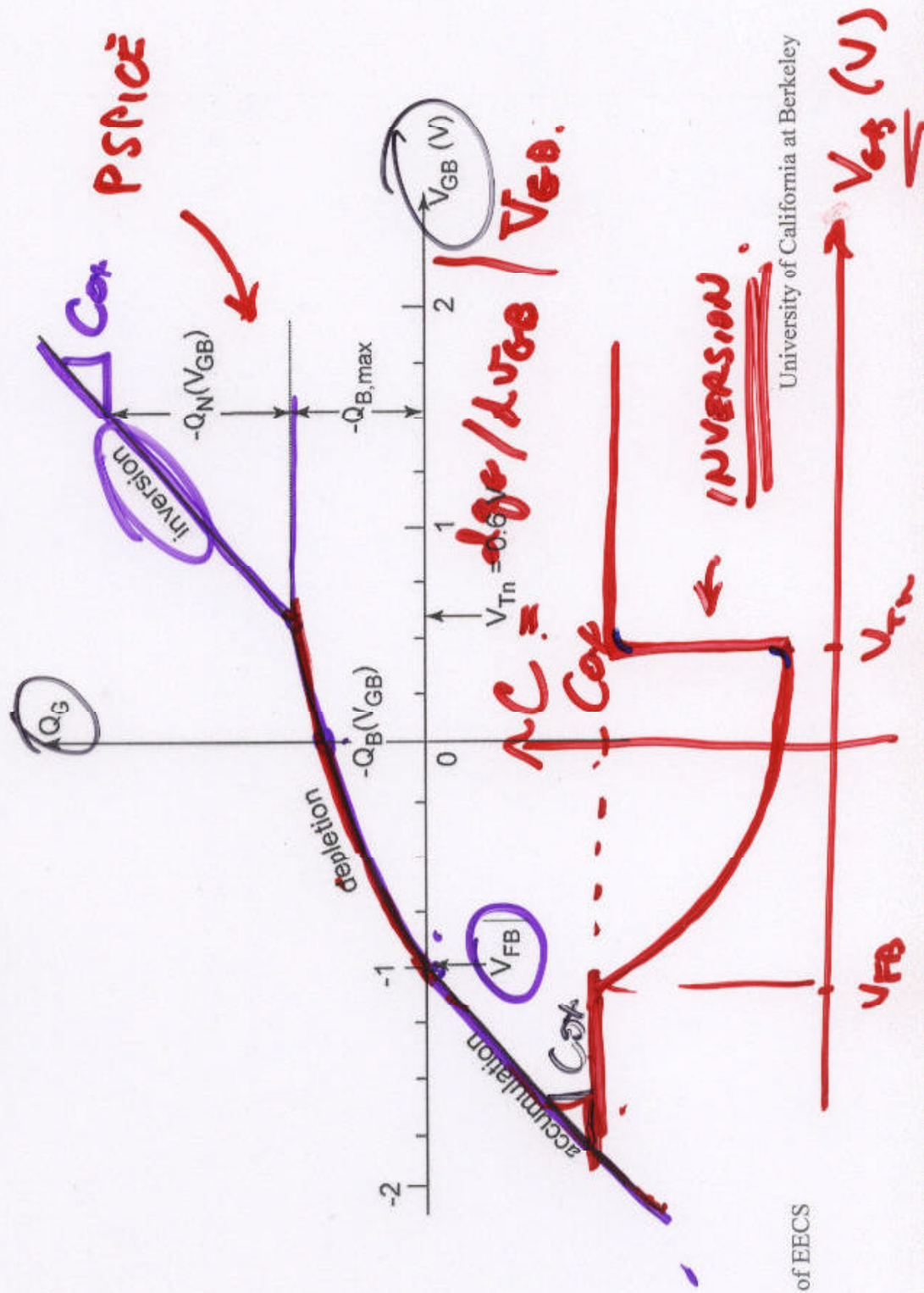


⊖ ionized acceptors
⊕ electrons in inversion layer



Increasing voltage \rightarrow additional charge stored in inversion layer

Charge vs. Voltage Curve



DERIVATIVE OF Q_c vs. V_{GB}

MOS Capacitance vs. Voltage

